

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306526	P-1598.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	Antonius T. A. M. DERKSEN <i>et al.</i>
Appln. No.:	Unknown
Filing Date:	November 12, 2003
Examiner:	Unknown
Group Art Unit:	Unknown

Date: November 12, 2003 Page 1 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (If appropriate)
PK	AR	3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
	BR	3,648,587	03/1972	Stevens	95	44	
	CR	4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
	DR	4,396,705	08/1983	Akeyama <i>et al.</i>	430	326	
	ER	4,480,910	11/1984	Takanashi <i>et al.</i>	355	30	
	FR	4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	GR	5,040,020	08/1991	Rauschenbach <i>et al.</i>	355	53	
	HR	5,121,256	06/1992	Corle <i>et al.</i>	359	664	
	IR	5,610,683	03/1997	Takahashi	355	53	
	JR	5,715,039	02/1998	Fukuda <i>et al.</i>	355	53	
	KR	5,825,043	10/1998	Suwa	250	548	
	LR	5,900,354	05/1999	Batchelder	430	395	
	MR	6,191,429	02/2001	Suwa	250	548	
PK	NR	6,560,032	05/2003	Hatano	359	656	

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						Enclosed	No	Enclose	No
PK	OR	WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>	X		X	
	PR	EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>	X			
	QR	EP 0418427	03/1991	Europe	Miyake	X		X	
	RR	EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>	X		X	
	SR	DD 224448	07/1985	German	Hesse <i>et al.</i>		X		
	TR	DD 242880	02/1987	German	Kuch		X		
	UR	FR 2474708	07/1981	France	Letellier		X		
PK	VR	JP 62-065326	03/1987	Japan	Moriuchi	X			
PK	WR	JP 62-121417	06/1987	Japan	Nakazawa	X			
PK	XR	JP 63-157419	06/1988	Japan	Nakasuji	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

PK	YR	EP Search Report for EP 02257938 dated September 25, 2003							
	ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001							
	AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356							
PK	BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002							

Examiner: *[Signature]* Date Considered: 3/18/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
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Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306781	P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	Joeri LOF <i>et al.</i>
Appln. No.:	Unknown
Filing Date:	November 12, 2003
Examiner:	Unknown
Group Art Unit:	Unknown

Date: November 12, 2003 Page 2 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PL	CCR 6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
	DDR 6,633,365	10/2003	Suenaga	355	53	
	EER 2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
	FFR 2003/0123040	07/2003	Almog	355	69	
PL	GGR 2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	HHR					
	IIR					
	JJR					
	KKR					
	LLR					
	MMR					
	NNR					
	OOR					
	PPR					

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	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
PL	QQR JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>	X			
	RRR JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>	X			
	SSR JP 06-124873	05/1994	Japan	Takahashi	X		X	
	TTR JP 07-220990	08/1995	Japan	Fukuda <i>et al.</i>	X			
	UUR JP 10-228661	08/1998	Japan	Kurokawa	X			
	VVR JP 10-255319	09/1998	Japan	Suenaga <i>et al.</i>	X			
	WWR JP 10-303114	11/1998	Japan	Suwa	X		X	
	XXR JP 10-340846	12/1998	Japan	Kudo	X		X	
PL	YYR JP 2001-091849	04/2001	Japan	Aizaki <i>et al.</i>	X			
	ZZR							

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PL	AAAR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography". TSMC, Inc., September 2002				
PL	BBBR	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997				

Examiner Pto B. J. Date Considered: 3 / 18 / 05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

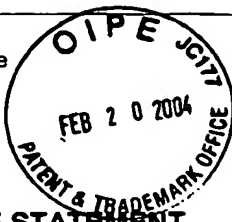
FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office		Atty. Dkt. No.	M#	Client Ref.
		306781		P-0381.010-US
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant: Joeri LOF <i>et al.</i>		
		Appln. No.: Unknown		
		Filing Date: November 12, 2003		
Date: November 12, 2003		Page 3 of 3	Examiner: Unknown	
		Group Art Unit: Unknown		

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
CCC						
DDD						
EEE						

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	FFFF								
	GGG								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)									
9K	HHH	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269							
	IIIR	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72							
	JJRS	S. Owa et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003							
	KKK	S. Owa et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)							
	LLL	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003							
	MMN	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36							
	NNN	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309							
	OOO	B.W. Smith et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003							
	PPP	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177							
9K	QQQ	G. Owen et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036							
	RRR								
	SSS								
	TTT								
	UUU								
	VVV								
	WWW								
	XXX								
	YYY								

Examiner <i>[Signature]</i>	Date Considered: 3/18/05
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Atty. Dkt. No.	M#	Client Ref.
081468	0306526	P-1598.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Antonius T.A.M. DERKSEN et al.

Appln. No.: 10/705,785

Filing Date: November 12, 2003

Examiner: Unassigned Group Art Unit: Unassigned

Date: February 20, 2004

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>PK</i>	AR 2004/0000627A1	01/01/2004	Karl-Heinz SCHUSTER			
<i>PK</i>	BR 6,600,547	07/29/2003	WATSON et al.			
<i>PK</i>	CR 2004/0021844 A1	02/05/2004	Yutaka SUENAGA			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

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							Enclosed	No	Enclose	No
	OR									
	PR									
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OTHER (including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

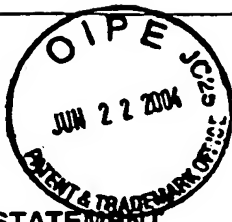
<i>PK</i>	YR	H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3			
<i>PK</i>	ZR	S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.			
	AAR				
	BBR				
	CCR				
	DDR				

Examiner *PK*

Date Considered: *3/18/05*

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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: DERKSEN et al.
Appln. No.: 10/705,785
Filing Date: November 12, 2003
Examiner: _____
Group Art Unit: 2882

Date: June 22, 2004

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PL	AR 2004/0075895 A1	04/2004	LIN			
PL	BR 2004/0109237 A1	06/2004	EPPL et al.			
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					

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	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
PL	IR JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.	X			
	JR JP 58-202448	11/1983	JAPAN	KAWAMURA et al.	X			
	KR WO2004/019128	03/2004	PCT	OMURA et al.				
	LR WO 03/077037	09/2003	PCT	ROSTALSKI				
	MR WO 03/077036	09/2003	PCT	SCHUSTER	X			
	NR DD 206 607	02/1984	GERMANY	WESTPHAL et al.		X		
PL	OR DD 221 563	04/1985	GERMANY	PFORR et al.		X		
	PR							
	QR							

OTHER (including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

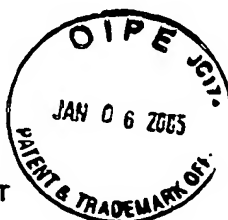
PL	RR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
	SR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
	TR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	UR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	VR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
PL	WR	B. LIN, "The k_3 coefficient in nonparaxial A/NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
	XR				
	YR				
	ZR				

Examiner *PLA B. Lin*

Date Considered: 3/18/05

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	0306526	P-1598.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: DERKSEN et al.
Appln. No. : 10/705,785
Filing Date: November 12, 2003
Examiner: Unknown
Group Art Unit: 2882

Date: January 6, 2005 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PK	AR	4,390,273	06/1983	LOEBACH et al.	355	125	
	BR	6,236,634 B1	05/2001	LEE et al.	369	112	
	CR	2002/0020821	02/2002	VAN SANTEN et al.	250	492	
PK	DR	2004/0119954	06/2004	KAWASHIMA et al.	355	30	
	ER	2004/0125351	07/2004	KRAUTSCHIK	355	53	

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		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
PK	FR	JP 2004-193252	07/2004	JAPAN	Not Available		X		
PK	GR	JP 11-176727	07/1999	JAPAN	SHIRAISHI	X			
PK	HR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.	X			
PK	IR	WO 2004/053950 A1	06/2004	PCT	OWA	X			
	JR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.	X			
	KR	WO 2004/053952 A1	06/2004	PCT	MAGOME et al.	X			
	LR	WO 2004/053953 A1	06/2004	PCT	NEI et al.	X			
	MR	WO 2004/053954 A1	06/2004	PCT	NEI et al.	X			
	NR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.	X			
	OR	WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.	X			
	PR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.	X			
	QR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.	X			
	RR	WO 2004/053959 A1	06/2004	PCT	SHIRAI	X			
	SR	WO 2004/053956 A2	06/2004	PCT	GRAUPNER	X			
	TR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X			
	UR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X			
PK	VR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

WR				
XR				
YR				
ZR				
AAR				
BBR				
CCR				
DDR				

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